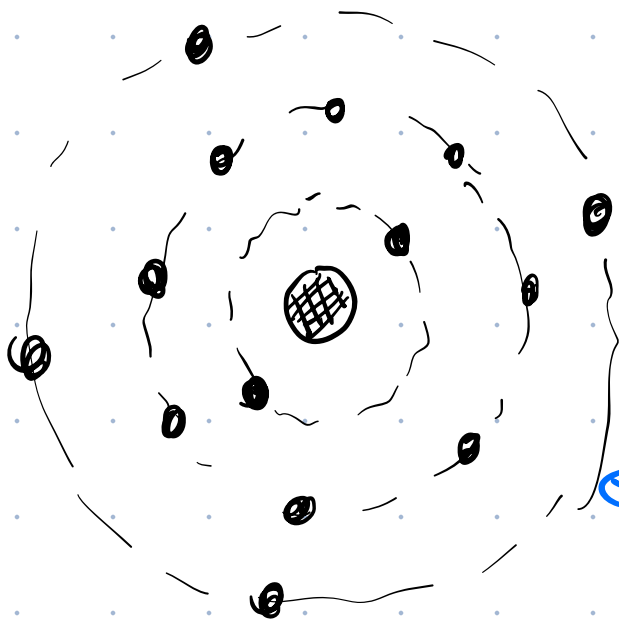


Today: Semiconductor Materials

Most semiconductor materials are Si, Si is 14th element in periodic table \Rightarrow 14 electron.



Nucleus has
14 protons &
14 neutrons
 \rightarrow charge +14

← Valence shell

Electrons in inner shells are called core electrons.

Electron Configuration of Si

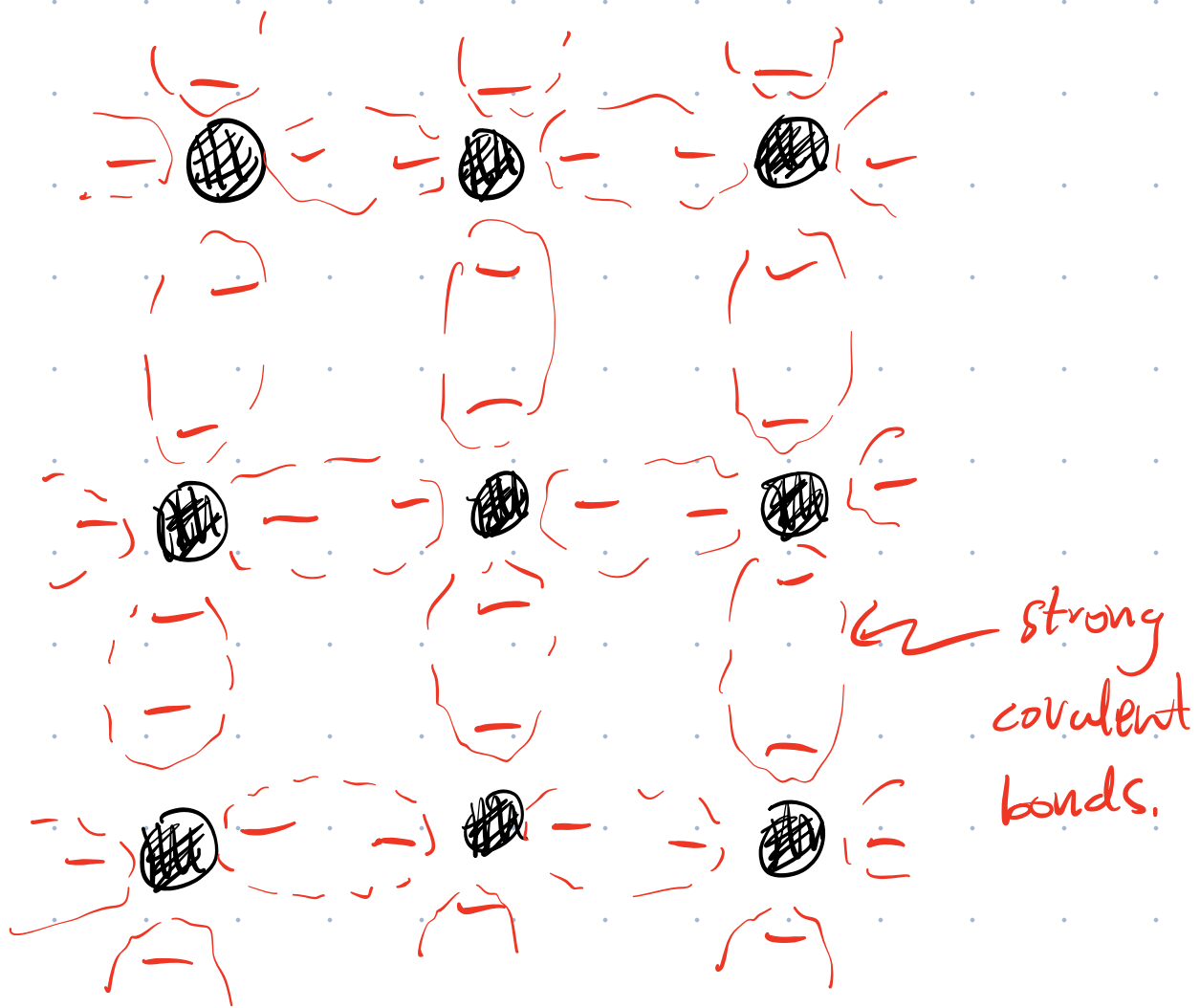


shell no. \rightarrow 1, 2, 3
orbital \rightarrow s, p
no. of e⁻ in the orbital \rightarrow 2, 2, 6, 2, 2

There is room for 4 more electrons in 3p orbital (it can take 6, but we've only placed 2).

Outer or valence shell is only partially filled.

2-D representation of a piece of solid Si.



⊗ represents Si nucleus + 10 core electrons
↪ charge +4

Each Si atom in the solid has 4 nearest neighbours.

Most valence e^- in pure Si participating in covalent bonds. No mobile or free charge available to conduct electricity.

Can create mobile charges by heating Si.

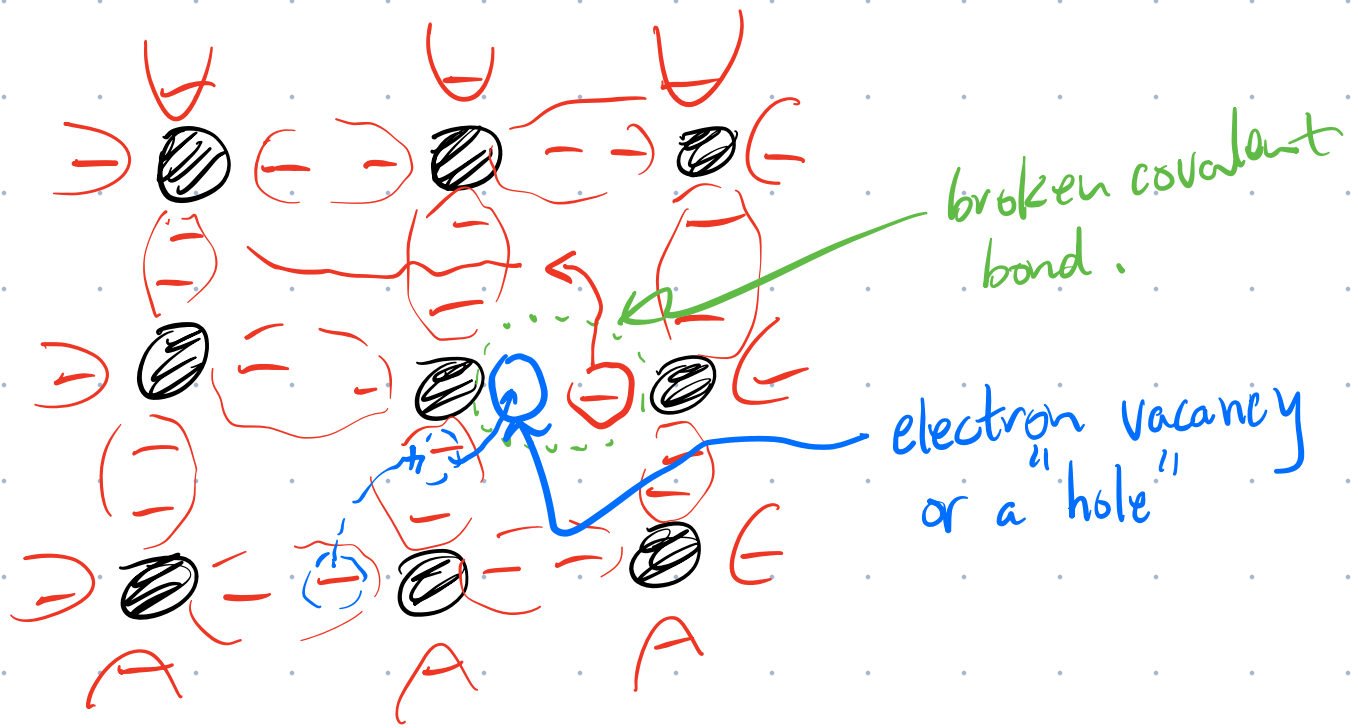
Energy Δ required to break a covalent bond is:

$$\Delta \sim 1.1 \text{ eV} = 1.8 \times 10^{-19} \text{ J}$$

$$\frac{\Delta}{k_B} \approx 12.7 \times 10^3 \quad (\text{high temp}).$$

Since $\frac{\Delta}{k_B} \ll T_{\text{rm}} \approx 300 \text{ K}$, Si is not a good conductor @ room temp.

At room temp. very few covalent bonds break (but more than zero).



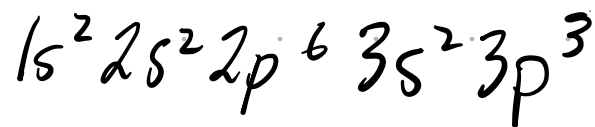
1. Each broken bond creates mobile electrons and mobile holes.
2. The mobile e^- & holes can conduct electricity (est. current).

We can manipulate the electronic properties of Si via "doping".

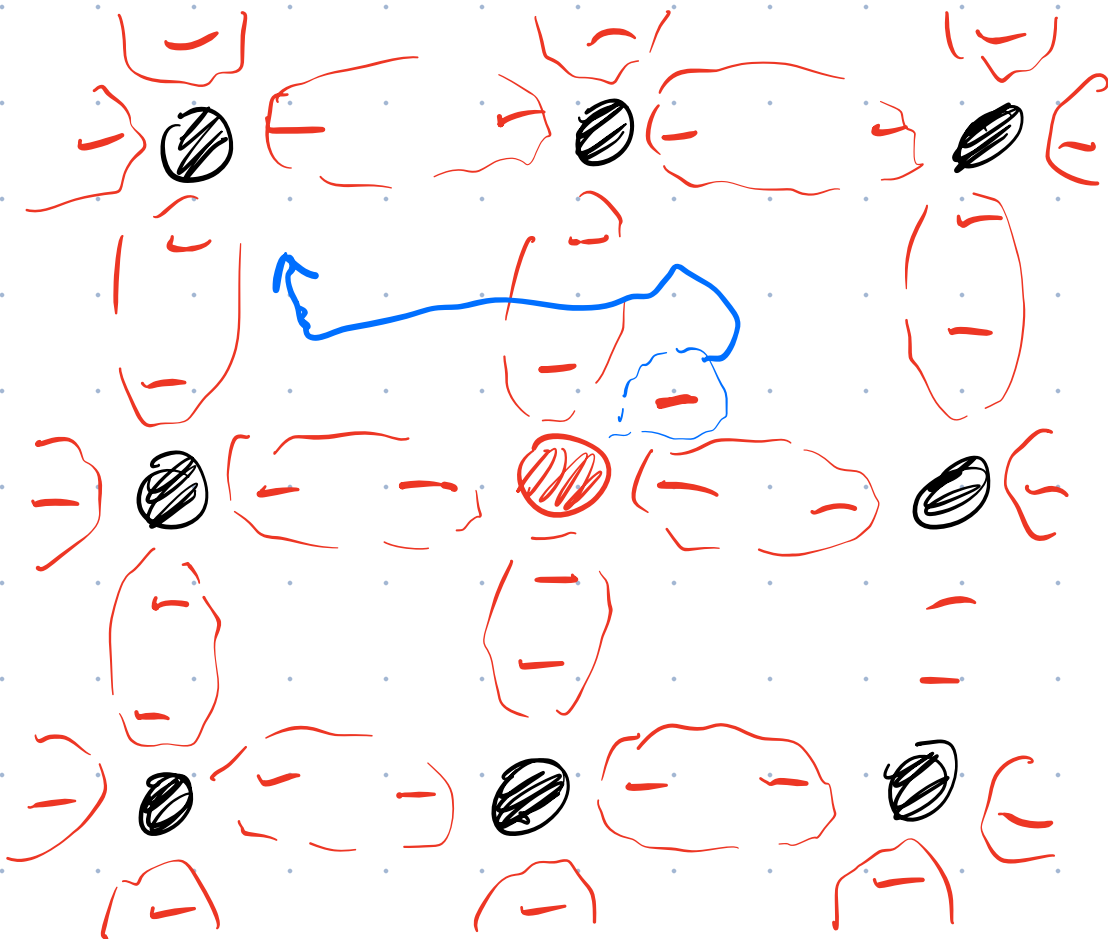
Try to replace an occasional Si atom with something that has either 5 or 3 valence e^- .

n-type doping (use dopant atoms w/ 5 valence e^-).
(electron doping)

Use P as dopant which has 5 valence e^- .
Electron config. of P:



Doping concentration typically can vary from
1 dopant per 1000 Si to 1 dopant per 10^9 Si.



- Si nucleus + 10 core electrons. Charge +4
- P nucleus + 10 core electrons. Charge +5

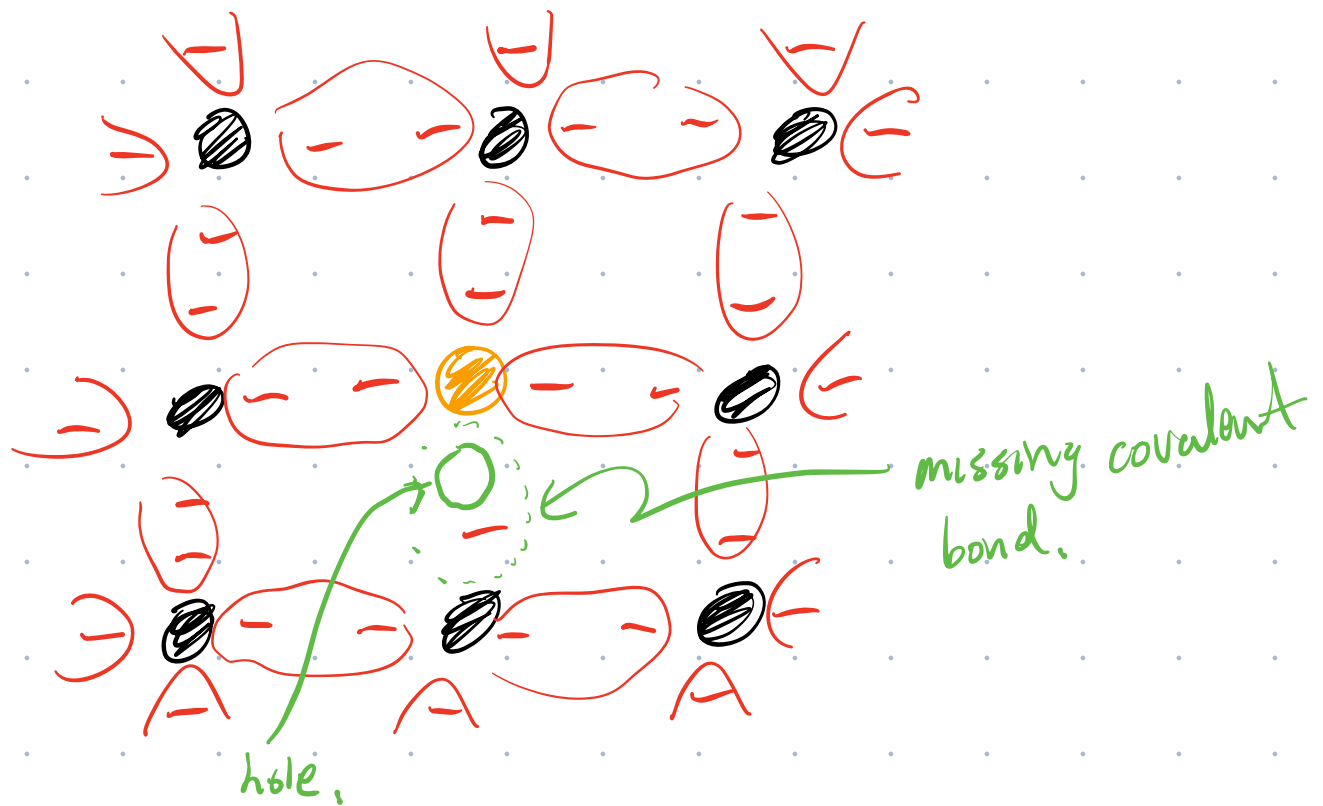
The extra valence e^- in the dopant is not participating in a covalent bond. It is only weakly attached to its host atom. It easily detaches and moves through the material.

p-type doping (hole doping)

Use a dopant w/ 3 valence e^- .

Eg. is Boron B. Electron config. is $1s^2 2s^2 2p^1$

2nd shell
is valence
shell.



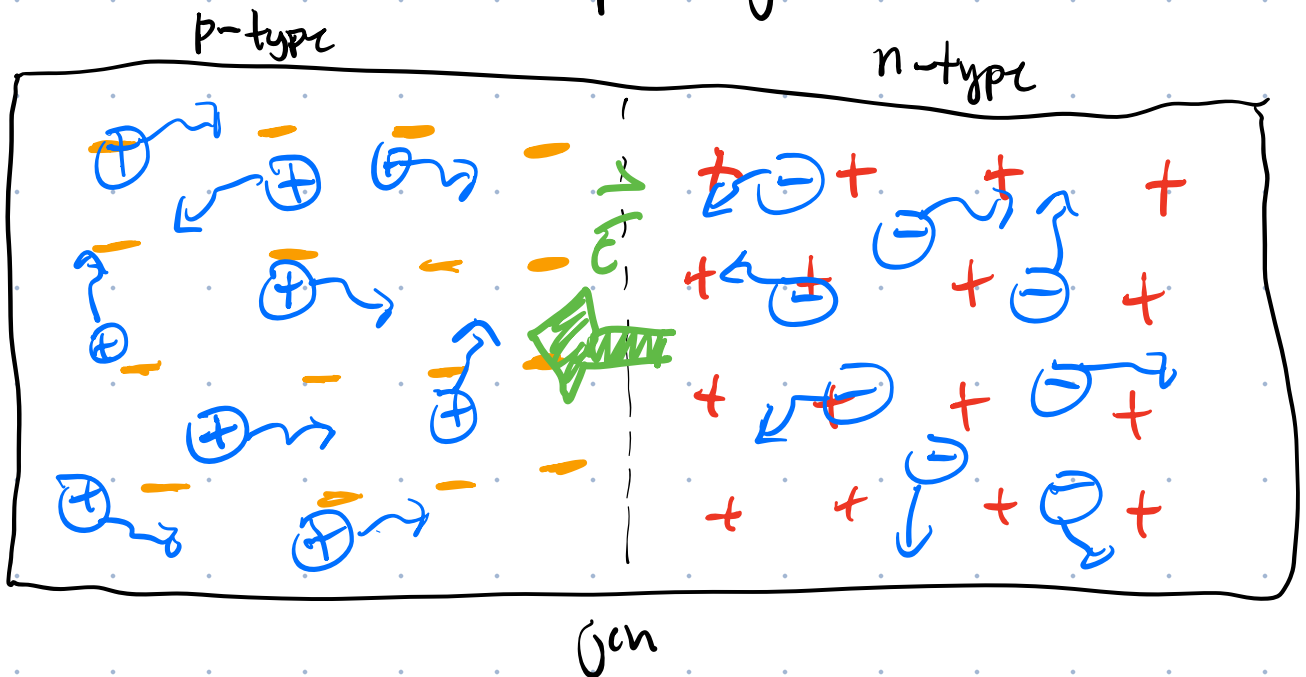
● Si nucleus + 10 core e^- . Charge +4.

● B nucleus + 2 core e^- . Charge +3.

Doping is used to introduce "majority" charge carriers. When a covalent bond is broken, due to thermal energy, the free e^- & hole that are created are called "minority" charge carriers.

Modern semiconductor devices (diodes & transistors) are made by joining n- & p-type doped semiconductors w/ a sharp junction.

Diode has a single p-n jcn.



- fixed neg. ions.

+ fixed pos. ions

(+) mobile holes

(-) mobile electrons.